What is Claimed is:

1. An apparatus for treating gaseous pollutants, comprising:

a gas inlet part, comprising a gas inlet chamber, at least one guide pipe and a cleaning element, the at least one guide pipe is substantially obliquely installed in the gas inlet chamber and communicating with the gas inlet chamber, the at least one guide pipe communicating with the gas inlet chamber and guiding an effluent stream from a semiconductor process to the gas inlet chamber, the cleaning element comprising a moving element and a cleaning head, the cleaning head connected to one end of the moving element, and the cleaning head configured to be driven by the moving element to move down to clean dust, particles or dirt adhering to the gas inlet chamber;

a water curtain scrubber, coupled to a bottom of the gas inlet part, configured to provide a water curtain to flush the gaseous pollutant to prevent dust or particles of the gaseous pollutant from adhering to a wall surface of the water curtain scrubber;

a circulating water tank, comprising a water collection space, a barrier, a first upper opening, a second upper opening, and a third upper opening, the barrier disposed in the water collection space and dividing the water collection space into a first region and a second region, the first region and the second region communicating with each other at a bottom of the water collection space, the first upper opening and the second upper opening communicating with the first region, the first upper opening coupled to the water curtain scrubber,

and the third upper opening communicating with the second region;

a first treatment unit, coupled to the second upper opening of the circulating water tank, and the first treatment unit comprising a plurality of sprays configured to abate the effluent stream, and first treatment unit comprising a top opening;

a non-mechanical flow-guiding device, coupled to the third upper opening of the circulating water tank, and coupled to the first treatment unit and configured to guide the effluent stream to move toward an opening; and

a second treatment unit, coupled to the non-mechanical flow-guiding device via the opening, the second treatment unit receiving the effluent stream from the first treatment unit and further abating the effluent stream;

wherein an inflow region is defined between the non-mechanical flow-guiding device and the first treatment unit, an outflow region is defined between the non-mechanical flow-guiding device and the second treatment unit, a first channel is formed between the outflow region and the inflow region,

wherein the non-mechanical flow-guiding device comprises a fluid supply tube and a flow-guiding tube, the fluid supply tube is in the shape of a cone with a wide top and a narrow bottom, the flow-guiding tube is in the shape of a cone with a narrow top and a wide bottom, the fluid supply tube and the flow-guiding tube are spaced apart from each other, and a second channel is positioned in the first channel and formed between the fluid supply tube and the flow-

guiding tube, wherein the fluid supply tube supplies an injection fluid to the flow-guiding tube, whereby a pressure difference is generated between the first channel and the second channel, and the pressure difference drives the gaseous pollutant to enter the outflow region from the inflow region.

2. The apparatus for treating gaseous pollutants according to claim 1, wherein the flow-guiding device induces a pressure difference with an injection fluid to guide movement of the effluent stream.

3. The apparatus for treating gaseous pollutants according to claim 1, wherein the first treatment unit and the second treatment unit are respectively a combustion type waste gas treater, a heating type waste gas treater, a wet type waste gas treater or a plasma type waste gas treater.